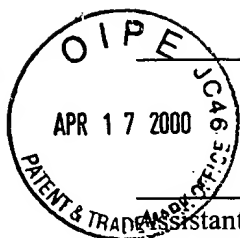


CPA/Gar 2823

Page 1



#11
4/25/00
Murphy
Continued

~~Asst. Dir.~~
Assistant Commissioner for Patents
Box CPA
Washington, D.C. 20231

This is a Request for filing a continuation application under 37 CFR 1.53(d) as a Continued Prosecution Application (CPA) of prior Application No. 09/037,945, filed on March 10, 1998, entitled STREAMLINED FIELD ISOLATION PROCESS, by inventors: Pierre C. Fazan, Viju K. Mathews, Nanseng Jeng

- (X) A 1-month extension for responding to the PTO communication mailed March 27, 2000, in the prior application is hereby requested.

Time Extension Fee:

- (X) One Month (\$110)

- (X) A preliminary amendment is enclosed.

The filing fee is calculated on the basis of the claims existing in the prior application as amended above.

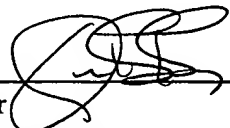
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TC 2800 MAIL ROOM
above.

FOR	NUMBER FILED	NUMBER EXTRA	RATE	FEE
Total Claims	11 - 20 =	0 ×	\$18	\$0
Independent Claims	4 - 3 =	1 ×	\$78	\$78
TEFERRA 00000035 09037945				
	78.00 OP	BASIC FEE		+ \$690
	690.00 OP			
	110.00 OP	TOTAL OF ABOVE CALCULATIONS		\$768
Time Extension Fee				\$110
TOTAL				\$878

- (X) The power of attorney in the prior application is to the law firm of Knobbe, Martens, Olson & Bear, LLP (Customer No. 20,995).
- (X) A check in the amount of \$878 is enclosed.
- (X) The Commissioner is hereby authorized to charge any additional fees under 37 CFR 1.16 and 1.17 which may be required, now or in the future, or credit any overpayment to Deposit Account No. 11-1410. A duplicate copy of this sheet is enclosed.
- (X) Return prepaid postcard.

Address all future communications to Customer No. 20,995.

Date: April 17, 2000

Signature: 

James B. Bear

Registration No. 25,221

Attorney of Record

INTELLECTUAL PROPERTY LAW
KNOBBE, MARTENS, OLSON & BEAR

A LIMITED LIABILITY PARTNERSHIP INCLUDING
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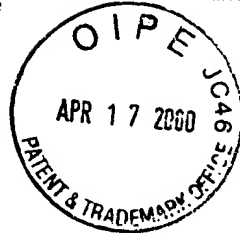
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† ALSO BARRISTER AT LAW (U.K.)
** U.S. PATENT AGENT

Assistant Commissioner for Patents
Washington, D.C. 20231

CERTIFICATE OF MAILING BY "EXPRESS MAIL"

Attorney Docket No. : MICRON.003C1

Applicants : Fazan et al.

For : STREAMLINED FIELD ISOLATION
PROCESS

Attorney : James B. Bear

"Express Mail"

Mailing Label No. : EL523239058

Date of Deposit : April 17, 2000

I hereby certify that the accompanying

Transmittal in Duplicate; Preliminary Amendment in 4 pages; Check for Filing
Fee; Return Prepaid Postcard

are being deposited with the United States Postal Service "Express Mail Post Office to
Addressee" service under 37 CFR 1.10 on the date indicated above and are addressed to the
Assistant Commissioner for Patents, Washington, D.C. 20231.


Arthur Greene

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PATENT

#12/D
4/25/00
Murphy

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants : Fazan et al.

Appl. No. : 09/037,945

Filed : March 10, 1998

For : STREAMLINED FIELD
ISOLATION PROCESS

Examiner : George Fourson

) Group Art Unit 2823

) I hereby certify that this correspondence and all
) marked attachments are being deposited with
) the United States Postal Service as first-class
) mail in an envelope addressed to: Assistant
) Commissioner for Patents, Washington, D.C.
) 20231, on

April 17, 2000

(Date)

James B. Bear, Reg. No. 25,221

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

This is a response to the Office Action mailed on March 27, 2000, in which all of the pending claims were finally rejected. This Preliminary Amendment amends all of the pending claims to clarify the claimed process in a manner which avoids the prior art without altering the principal focus of the claims.

In the Claims:

D1 1. (Thrice Amended) A process of forming an integrated circuit, comprising:
growing a silicon dioxide field isolation region on a semiconductor wafer
without forming silicon nitride inclusions in said field isolation region exclusively by means
of a hydrogen-free oxidant at a pressure less than about 30 atm; and forming a gate oxide
without a prior sacrificial oxidation.

D2 5. (Thrice Amended) A field isolation region among integrated circuit devices on a
semiconductor substrate formed by a process comprising:
avoiding the formation of silicon nitride inclusions in the field isolation region by
exposing a field region of the semiconductor substrate to a hydrogen-free oxidizing ambient
at a pressure between about 5 atm and 30 atm.